Philippe Allongue

List of Publications by Year
in descending order

138 papers	6,912 citations	87888 38 h-index	62596 80 g-index
154 all docs	154 docs citations	154 times ranked	5277 citing authors

#	Article	IF	Citations
1	OperandoIdentification of the Reversible Skin Layer on Co₃O₄as a Three-Dimensional Reaction Zone for Oxygen Evolution. ACS Catalysis, 2022, 12, 3256-3268.	11.2	28
2	Insights into the Ochratoxin A/Aptamer Interactions on a Functionalized Silicon Surface by Fourier Transform Infrared and UVâ€“Vis Studies. Langmuir, 2020, 36, 13908-13917.	3.5	11
3	Electrochemical Stability of the Reconstructed Fe₃O₄(001) Surface. Angewandte Chemie, 2020, 132, 22088-22092.	2.0	0
4	Electrochemical Stability of the Reconstructed Fe₃O₄(001) Surface. Angewandte Chemie - International Edition, 2020, 59, 21904-21908.	13.8	22
5	In situ monitoring of electric field effect on domain wall motion in Co ultrathin films in direct contact with an electrolyte. Applied Physics Letters, 2019, 115, .	3.3	7
6	Structure of Mixed Acid/Decyl Monolayers Grafted on Oxide-Free Si(111) Surfaces. Langmuir, 2019, 35, 2547-2553.	3.5	3
7	Influence of Light Polarization on Photoswitching of Fulgimide Monolayers on Surfaces. Journal of Physical Chemistry C, 2019, 123, 12223-12233.	3.1	2
8	Operando Surface X-ray Diffraction Studies of Structurally Defined Co₃O₄ and CoOOH Thin Films during Oxygen Evolution. ACS Catalysis, 2019, 9, 3811-3821.	11.2	93
9	Direct Li+ incorporation during the anodic formation of compact TiO2 layers. Chemical Communications, 2018, 54, 3251-3254.	4.1	3
10	Potential dependence of the structure and magnetism of electrodeposited Pd/Co/Au(111) layers. Journal of Electroanalytical Chemistry, 2018, 819, 322-330.	3.8	9
11	Transmission Surface Diffraction for Operando Studies of Heterogeneous Interfaces. Journal of Physical Chemistry Letters, 2017, 8, 1067-1071.	4.6	16
12	Epitaxial Electrodeposition of Fe on Au(111): Structure, Nucleation, and Growth Mechanisms. Journal of Physical Chemistry C, 2016, 120, 16080-16089.	3.1	18
13	Electrochemical de-alloying in two dimensions: role of the local atomic environment. Nanoscale, 2016, 8, 13985-13996.	5.6	6
14	Influence of Potential on the Electrodeposition of Co on Au(111) by In Situ STM and Reflectivity Measurements. Journal of the Electrochemical Society, 2016, 163, D3062-D3068.	2.9	7
15	In-situ infrared study of silicon in KOH electrolyte: Surface hydrogenation and hydrogen penetration. Surface Science, 2016, 644, 180-190.	1.9	4
16	Film and Interface Atomic Structures of Electrodeposited Co/Au(111) Layers: An in Situ X-ray Scattering Study as a Function of the Surface Chemistry and the Electrochemical Potential. Journal of Physical Chemistry C, 2016, 120, 3360-3370.	3.1	10
17	Oxide Formation and Dissolution on Silicon in KOH Electrolyte: An In-Situ Infrared Study. Journal of the Electrochemical Society, 2016, 163, H327-H338.	2.9	8
18	Electrodeposition of Ag, Pd and Au on Ni monolayer islands on (1 Ã— 1)-Au(111) by in-situ scanning tunneling microscopy. Electrochimica Acta, 2016, 197, 241-250.	5.2	9

#	Article	IF	Citations
19	In situ surface X-ray diffraction study of ultrathin epitaxial Co films on Au(111) in alkaline solution. Electrochimica Acta, 2016, 197, 273-281.	5.2	16
20	Influence of controlled surface oxidation on the magnetic anisotropy of Co ultrathin films. Applied Physics Letters, 2015, 106, .	3.3	27
21	Ni electrochemical epitaxy on unreconstructed Au(111): An in-situ STM study. Surface Science, 2015, 631, 135-140.	1.9	3
22	Probing the electrochemical interface with in situ magnetic characterizations: A case study of Co/Au(111) layers. Surface Science, 2015, 631, 88-95.	1.9	8
23	Poly(dimethylsiloxane) as a pre-coating in layer-by-layer films containing phosphotungstate nanoclusters electrochemically sensitive toward s-triazines. RSC Advances, 2014, 4, 29612.	3.6	10
24	Thermal decomposition of alkoxy monolayers grafted on silicon: A mechanistic model. Surface Science, 2013, 609, 230-235.	1.9	1
25	Electrodeposition of NiPd monolayer on Au(111): An in situ scanning tunneling microscopy study. Electrochimica Acta, 2013, 112, 824-830.	5.2	3
26	Quantitative IR Readout of Fulgimide Monolayer Switching on Si(111) Surfaces. Advanced Materials, 2013, 25, 416-421.	21.0	10
27	AuNi alloy monolayer films electrodeposited on Au(111): An in situ STM study. Surface Science, 2013, 607, 25-32.	1.9	7
28	Improved chemical and electrical stability of gold silicon contacts via epitaxial electrodeposition. Journal of Applied Physics, 2013, 113, 063708.	2.5	5
29	Influence of the surface chemistry on the electric-field control of the magnetization of ultrathin films. Physical Review B, 2012, 86, .	3.2	24
30	Organic Grafting on Si for Interfacial SiO₂ Growth Inhibition During Chemical Vapor Deposition of HfO₂. Chemistry of Materials, 2012, 24, 3135-3142.	6.7	5
31	Kinetics of Activation of Carboxyls to Succinimidyl Ester Groups in Monolayers Grafted on Silicon: An in Situ Real-Time Infrared Spectroscopy Study. Journal of Physical Chemistry C, 2011, 115, 6782-6787.	3.1	17
32	Spin-dependent photoelectron tunneling from GaAs into magnetic cobalt. Physical Review B, 2011, 83, .	3.2	3
33	(Invited) Functionalization and Behavior in Aqueous Media of Silicon Surfaces for Improved Biochemical Sensing. ECS Transactions, 2011, 35, 101-107.	0.5	0
34	Covalent Functionalizations of Silicon Surfaces and Their Application to Biosensors. Science of Advanced Materials, 2011, 3, 332-353.	0.7	23
35	In situ monitoring of the electronic properties and the pH stability of grafted Si(111). Journal of Electroanalytical Chemistry, 2010, 646, 33-42.	3.8	20
36	Epitaxial Growth of Gold on Hï£¿Si(111): The Determining Role of Hydrogen Evolution. ChemPhysChem, 2010, 11, 2992-3001.	2.1	15

#	Article	IF	Citations
37	Molecular monolayers on silicon as substrates for biosensors. Bioelectrochemistry, 2010, 80, 17-25.	4.6	32
38	Electrochemical growth and dissolution of Ni on bimetallic Pd/Au(111) substrates. Electrochimica Acta, 2010, 55, 8087-8099.	5.2	11
39	Covalent immobilization of amino acids on the porous silicon surface. Surface and Interface Analysis, 2010, 42, 515-518.	1.8	17
40	Electrodeposited magnetic layers in the ultrathin limit. MRS Bulletin, 2010, 35, 761-770.	3.5	23
41	Semiquantitative Study of the EDC/NHS Activation of Acid Terminal Groups at Modified Porous Silicon Surfaces. Langmuir, 2010, 26, 809-814.	3.5	311
42	Functionalized Silicon Surfaces for Biological and Chemical Sensors. Sensor Letters, 2010, 8, 447-456.	0.4	2
43	Selective Growth and Dissolution of Ni on a PdAu Bimetallic Surface byInÂSituSTM: Determining the Relative Adsorbate-Substrate Interaction Energy. Physical Review Letters, 2009, 102, 196101.	7.8	13
44	Electrochemical Growth Gold Buffer Layer on H-Si(111) Surfaces and Their Applications. ECS Transactions, 2009, 19, 197-207.	0.5	0
45	Electronic Properties and pH Stability of Si(111)/Alkyl Monolayers. ECS Transactions, 2009, 19, 373-379.	0.5	3
46	In Situ Infrared Kinetic Study of Multistep Chemical Modifications of Organic Monolayers at Silicon Surfaces. ECS Transactions, 2009, 19, 283-292.	0.5	5
47	Highly sensitive and reusable fluorescence microarrays based on hydrogenated amorphous siliconâ€“carbon alloys. Biosensors and Bioelectronics, 2009, 25, 952-955.	10.1	13
48	Magnetism of electrodeposited ultrathin layers: Challenges and opportunities. Surface Science, 2009, 603, 1831-1840.	1.9	25
49	Electrochemical Au deposition on stepped Si(111)-H surfaces: 3D versus 2D growth studied by AFM and X-ray diffraction. Surface Science, 2009, 603, 1212-1220.	1.9	10
50	Electrochemical transfer at p-type silicon(111)-alkyl monolayer hybrid electrodes in acetonitrile medium. Journal of Electroanalytical Chemistry, 2009, 629, 63-68.	3.8	7
51	Controlled Oxidation of Alkyl Monolayers Grafted onto Flat Si(111) in an Oxygen Plasma of Low Power Density. Journal of Physical Chemistry C, 2009, 113, 14418-14428.	3.1	9
52	Single-step electrochemical nanolithography of metal thin films by localized etching with an AFM tip. Nanotechnology, 2008, 19, 325301.	2.6	24
53	The Titration of Carboxyl-Terminated Monolayers Revisited: In Situ Calibrated Fourier Transform Infrared Study of Well-Defined Monolayers on Silicon. Langmuir, 2008, 24, 9440-9448.	3.5	47
54	Electrochemical growth of ultraflat Au(111) epitaxial buffer layers on Hâ€“Si(111). Applied Physics Letters, 2008, 93, .	3.3	38

#	Article	IF	Citations
55	In-situ IR Spectroscopy to Study Anodic Oxidation of Si(111) in KOH Solution. ECS Transactions, 2007, 6, 481-488.	0.5	2
56	Quantitative Infrared Investigation of the Acido-Basic Equilibrium at a Carboxy-Terminated Silicon Surface. ECS Transactions, 2007, 6, 475-479.	0.5	0
57	Mechanisms of Thermal Decomposition of Organic Monolayers Grafted on (111) Silicon. Langmuir, 2007, 23, 1326-1332.	3.5	24
58	Analysis of CapacitancePotential Measurements at the Siliconâ^'Electrolyte Interface Revisited. Journal of Physical Chemistry C, 2007, 111, 5497-5499.	3.1	10
59	Thermal stability of alkoxy monolayers grafted on Si(111). Surface Science, 2007, 601, 3961-3964.	1.9	14
60	Preparation, characterization and magneto-optical investigations of electrodeposited Co/Au films. Journal of Magnetism and Magnetic Materials, 2007, 315, 26-38.	2.3	18
61	Well-Defined Carboxyl-Terminated Alkyl Monolayers Grafted onto Hâ^'Si(111):Â Packing Density from a Combined AFM and Quantitative IR Study. Langmuir, 2006, 22, 153-162.	3.5	172
62	Water Exclusion at the Nanometer Scale Provides Long-Term Passivation of Silicon (111) Grafted with Alkyl Monolayers. Journal of Physical Chemistry B, 2006, 110, 5576-5585.	2.6	54
63	Metal electrodeposition on single crystal metal surfaces mechanisms, structure and applications. Current Opinion in Solid State and Materials Science, 2006, 10, 173-181.	11.5	51
64	Iron passivation studied by in situ Raman spectroscopy on Fe/Au(111) epitaxial films. , 2006, , 89-94.		2
65	Perpendicular anisotropy in electrodeposited Au/Co films. Physica B: Condensed Matter, 2006, 384, 138-140.	2.7	3
66	Self-ordered electrochemical growth on single-crystal electrode surfaces. Journal of Physics Condensed Matter, 2006, 18, S97-S114.	1.8	20
67	Thermal decomposition of alkyl monolayers covalently grafted on (111) silicon. Applied Physics Letters, 2006, 88, 193123.	3.3	28
68	Structure sensitivein situRaman study of iron passive films using SERS-activeFeâ^•Au(111)substrates. Physical Review B, 2005, 71, .	3.2	17
69	Truly Quantitative XPS Characterization of Organic Monolayers on Silicon: Study of Alkyl and Alkoxy Monolayers on Hâ^'Si(111). Journal of the American Chemical Society, 2005, 127, 7871-7878.	13.7	182
70	Intralayer coupling in self-organized Fe nanoclusters grown on vicinal Si(111). Physical Review B, 2004, 70, .	3.2	17
71	Electrodeposition of Fe/Au(111) ultrathin layers with perpendicular magnetic anisotropy. Physica B: Condensed Matter, 2004, 354, 282-285.	2.7	16
72	Electrodeposition of Co and Ni/Au(111) ultrathin layers. Part I: nucleation and growth mechanisms from in situ STM. Surface Science, 2004, 557, 41-56.	1.9	86

#	Article	IF	Citations
73	Semiconducting photocathodes for the reduction of dioxygen. Electrochimica Acta, 2004, 49, 4577-4582.	5.2	6
74	Electrochemically Grown Tin Oxide Thin Films:â€‰ In Situ Characterization of Electronic Properties and Growth Mechanism. Journal of Physical Chemistry B, 2004, 108, 8173-8181.	2.6	15
75	Electrochemical Micromachining of p-Type Siliconâ€. Journal of Physical Chemistry B, 2004, 108, 14434-14439.	2.6	52
76	Phenyl layers on Hâ€“Si(111) by electrochemical reduction of diazonium salts: monolayer versus multilayer formation. Journal of Electroanalytical Chemistry, 2003, 550-551, 161-174.	3.8	164
77	Electrochemical growth of gold on well-defined vicinal Hâ€“Si(111) surfaces studied by AFM and XRD. Surface Science, 2003, 537, 95-112.	1.9	39
78	Electrochemical Characterization of the Open-Circuit Deposition of Platinum on Silicon from Fluoride Solutions. Journal of Physical Chemistry B, 2003, 107, 6454-6461.	2.6	51
79	Strong dependence of the Fe thin-film magnetic anisotropy on the Si(111) substrate preparation. Journal of Applied Physics, 2003, 94, 1490-1494.	2.5	12
80	In- situ magnetic measurements of electrodeposited ultrathin Co, Ni and Fe/Au(111) layers. Physical Chemistry Chemical Physics, 2001, 3, 3330-3335.	2.8	35
81	Cu Electroplating on H-Terminated n-Si(111): Properties and Structure of n-Si/Cu Junctions. Journal of the Electrochemical Society, 2001, 148, C614.	2.9	32
82	Conducting Probe-Mediated Electrochemical Nanopatterning of Molecular Materials. Journal of the American Chemical Society, 2001, 123, 11486-11487.	13.7	17
83	Magnetic properties of electrodeposited Fe/Au(111) layers:. Journal of Magnetism and Magnetic Materials, 2001, 226-230, 1616-1617.	2.3	11
84	Enhanced interface perpendicular magnetic anisotropy in electrodeposited Co/Au(111) layers. Physical Review B, 2001, 63, .	3.2	71
85	Structural characterization of organic monolayers on Siã€˜111ã€‰ from capacitance measurements. Electrochimica Acta, 2000, 45, 3241-3248.	5.2	101
86	Anion effect in Co/Au(111) electrodeposition: structure and magnetic behavior. Applied Surface Science, 2000, 164, 22-28.	6.1	56
87	The preparation of flat Hâ€“Si(111) surfaces in 40% NH4F revisited. Electrochimica Acta, 2000, 45, 4591-4598.	5.2	157
88	Charge Exchange Processes during the Open-Circuit Deposition of Nickel on Silicon from Fluoride Solutions. Journal of the Electrochemical Society, 2000, 147, 1026.	2.9	90
89	Insights into the Formation Mechanisms of Siâˆ’OR Monolayers from the Thermal Reactions of Alcohols and Aldehydes with Si(111)âˆ’H1. Langmuir, 2000, 16, 7429-7434.	3.5	199
90	Electrochemical Micromachining. Science, 2000, 289, 98-101.	12.6	551

#	Article	IF	Citations
91	Molecularly Tunable â€œOrganic Capacitorsâ€at Silicon/Aqueous Electrolyte Interfaces1. Journal of Physical Chemistry B, 2000, 104, 11157-11161.	2.6	96
92	Organic monolayers on Si(111) by electrochemical method. Electrochimica Acta, 1998, 43, 2791-2798.	5.2	184
93	Electrochemical Formation of Close-Packed Phenyl Layers on Si(111). Journal of Physical Chemistry B, 1997, 101, 2415-2420.	2.6	316
94	Covalent Modification of Carbon Surfaces by Aryl Radicals Generated from the Electrochemical Reduction of Diazonium Salts. Journal of the American Chemical Society, 1997, 119, 201-207.	13.7	978
95	Anion promoted Ni-underpotential deposition on Au(111). Surface Science, 1997, 384, L836-L843.	1.9	30
96	Digital computation and in situ STM approach of silicon anisotropic etching. Surface Science, 1997, 388, 50-62.	1.9	42
97	Relationship between porous silicon formation and hydrogen incorporation. Thin Solid Films, 1997, 297, 1-4.	1.8	29
98	Molecular Grafting on Si(111) Surfaces: An Electrochemical Approach. Materials Research Society Symposia Proceedings, 1996, 451, 185.	0.1	16
99	Molecular Imaging and Local Density of States Characterization at the Si(111)/NaOH Interface. Physical Review Letters, 1996, 77, 1986-1989.	7.8	60
100	Etching mechanism and atomic structure of H-Si(111) surfaces prepared in NH4F. Electrochimica Acta, 1995, 40, 1353-1360.	5.2	169
101	Evidence for hydrogen incorporation during porous silicon formation. Applied Physics Letters, 1995, 67, 941-943.	3.3	72
102	Atomic Structure of Si Surfaces Etched in Triton/NaOH Solutions. The Journal of Physical Chemistry, 1995, 99, 9472-9478.	2.9	18
103	Probing by in situ scanning tunneling microscopy the influence of an organic additive on Si etching in NaOH. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1994, 12, 1539.	1.6	7
104	Monte-Carlo Simulations of Si Etching: Comparison with in-situ STM images. Microscopy Microanalysis Microstructures, 1994, 5, 257-267.	0.4	6
105	Structure of Si(111) surfaces etched in 40% NH4F: Influence of the doping. Microscopy Microanalysis Microstructures, 1994, 5, 291-299.	0.4	13
106	Metal electrodeposition on semiconductors. Journal of Electroanalytical Chemistry, 1993, 362, 79-87.	3.8	46
107	Metal electrodeposition on semiconductors. Journal of Electroanalytical Chemistry, 1993, 362, 89-95.	3.8	40
108	Influence of the doping concentration on the electrochemical etching of semiconductors. Electrochimica Acta, 1993, 38, 889-895.	5.2	8

#	Article	IF	Citations
109	Etching of Silicon in NaOH Solutions: II . Electrochemical Studies of nâ€Si(111) and (100) and Mechanism of the Dissolution. Journal of the Electrochemical Society, 1993, 140, 1018-1026.	2.9	241
110	Etching of Silicon in NaOH Solutions: I . In Situ Scanning Tunneling Microscopic Investigation of nâ€Si(111). Journal of the Electrochemical Society, 1993, 140, 1009-1018.	2.9	220
111	The Mechanism of the Anodic Oxidation of Silicon in Acidic Fluoride Solutions Revisited. Zeitschrift Fur Elektrotechnik Und Elektrochemie, 1993, 97, 753-757.	0.9	100
112	In situ STM observations of the etching of n-Si(111) in NaOH solutions. Surface Science, 1992, 275, 414-423.	1.9	88
113	Experimental investigation of charge transfer at the semiconductor/electrolyte junction. Electrochimica Acta, 1992, 37, 781-797.	5.2	34
114	Corrosion of IIIâ€“V compounds; a comparative study of GaAs and InP. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1991, 317, 77-99.	0.1	29
115	Study of reaction coupling and interfacial kinetics at semiconductor electrodes by band edge shift measurements. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1991, 300, 261-281.	0.1	25
116	Corrosion of III-V compounds; a comparative study of GaAs and InP. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1991, 316, 57-77.	0.1	16
117	Metal electrodeposition on semiconductors. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1990, 286, 217-237.	0.1	81
118	Charge Transfer Process at Illuminated Semiconductor/Electrolyte Junctions Modified by Electrodeposition of Microscopic Metal Grain. Journal of the Electrochemical Society, 1989, 136, 1027-1033.	2.9	38
119	On the kinetics of charge transfer between an illuminated CdSe electrode and polysulphide electrolyte. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1989, 269, 295-304.	0.1	11
120	Semiconductor electrode modifications: influence on the state distribution at the interface. Electrochimica Acta, 1989, 34, 1717-1722.	5.2	17
121	Semiconductor electrodes modified by electrodeposition of discontinuous metal films. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1989, 269, 361-374.	0.1	18
122	Charge transfer and stabilization at illuminated n-GaAs/aqueous electrolyte junctions. Electrochimica Acta, 1988, 33, 79-87.	5.2	28
123	Photoelectrochemical behaviour of GaAs modified by electrodeposition of heteropolyanions. Electrochimica Acta, 1988, 33, 693-699.	5.2	8
124	Steady State Photocapacitance Study of Semiconductor/Electrolyte Junctions II. Surface State Distribution and Charge Transfer Mechanisms. Zeitschrift Fur Elektrotechnik Und Elektrochemie, 1988, 92, 895-903.	0.9	27
125	Steady State Photocapacitance Study of Semiconductor/Aqueous Electrolyte Junctions: I. Interest and Difficulties in the Case of nâ€GaAs. Zeitschrift Fur Elektrotechnik Und Elektrochemie, 1988, 92, 566-572.	0.9	10
126	Stabilization of nâ€‰â€â€‰GaAs in Acidic Concentrated Iodide Electrolytes. Journal of the Electrochemical Society, 1987, 134, 620-625.	2.9	20

#	Article	IF	Citations
127	Schottky barrier formation of various metals on n-GaAs (100) by electrochemical deposition. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 1987, 5, 1644.	1.6	54
128	Photocapacitance study of nâ€GaAs/electrolyte interfaces. Zeitschrift Fur Elektrotechnik Und Elektrochemie, 1987, 91, 386-390.	0.9	23
129	Comparison between metal and electrolyte/(IIIâ€“V) semiconductor interfaces. Surface Science, 1986, 168, 356-364.	1.9	12
130	Flatband potential determination and surface modifications at semiconductor-liquid junctions. Solid State Communications, 1985, 55, 49-53.	1.9	26
131	Bandâ€Edge Shift and Surface Charges at Illuminated nâ€‰â€â€‰GaAsâ€‰/â€‰Aqueous Electrolyte Junctions: Surfaceâ€State Analysis and Simulation of Their Occupation Rate. Journal of the Electrochemical Society, 1985, 132, 45-52.	2.9	79
132	Photodissolution Kinetics of nâ€‰â€â€‰GaAs in 1Mâ€‰KOHâ€‰ and Calculation of the Stabilization by Se2â^' : Effect of the Ru3+ Surface Treatment. Journal of the Electrochemical Society, 1984, 131, 2861-2668.	2.9	47
133	Iâ€“V curve and surface state capacitance at illuminated semiconductor/liquid contacts. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1984, 176, 369-375.	0.1	11
134	Quantitative Comparison of Fermi Level Pinning at GaAsâ€‰/â€‰Metal and GaAsâ€‰/â€‰Liquid Junctions. Journal of the Electrochemical Society, 1984, 131, 2563-2569.	2.9	42
135	Detailed Analysis of a Redox Stabilized Liquid Junction Solar Cell: Application to the Cell. Journal of the Electrochemical Society, 1983, 130, 2352-2357.	2.9	37
136	Photoelectrochemical behaviour of an n-type GaAs electrode studied by impedance measurements. Determination and simulation of the faradaic resistance. Journal of Electroanalytical Chemistry and Interfacial Electrochemistry, 1981, 119, 371-377.	0.1	14
137	Electrodeposition of Two-Dimensional Magnetic Nanostructures on Single Crystal Electrode Surfaces. , 0, , 217-241.		1
138	Electrochemical surface processing of semiconductors at the atomic level. , 0, , 240-252.		0